

**AMENDMENTS TO THE CLAIMS**

**This listing of claims will replace all prior versions and listings of claims in the application:**

**LISTING OF CLAIMS:**

1. (currently amended): A method of manufacturing a lithography mask blank on a glass substrate, comprising the steps of:

depositing, on the glass substrate, at least one light absorption film which has a property of absorbing a laser beam of a predetermined wavelength ~~transmitted through~~ which transmits the glass substrate; and

irradiating a the laser beam of the predetermined wavelength onto the light absorption film to selectively heat the light absorption film and to thereby alleviate its internal stress.

2. (original): A method as claimed in claim 1, wherein the mask blank is a phase shift mask blank while the light absorption film is formed by a translucent film which serves as a phase shift film of the phase shift mask blank so as to attenuate exposure light of predetermined intensity.

3. (original): A method as claimed in claim 1, wherein the light absorption film is an opaque film.

4. (original): A method as claimed in claim 1, wherein the laser beam is irradiated onto the mask blank so that the transparent glass substrate with the light absorption film has flatness not greater than 0.5 micron meter.

5. (original): A lithography mask blank manufactured by the method claimed in claim 1.

6. (original) A lithography mask manufactured by the use of the mask blank claimed in claim 5.

Amendment under 37 C.F.R. § 1.312  
Application No. 09/998,422

7. (currently amended): A method of manufacturing a lithography mask blank as claimed in claim 1 wherein the step of irradiating comprises heating the light absorption film for a period on the order of several tens of nanoseconds.

8. (currently amended): A method of manufacturing a lithography mask blank as claimed in claim 1 wherein the step of irradiating comprises heating the light absorption film to a temperature of at least 1000°C.

9. (currently amended): A method of manufacturing a lithography mask blank as claimed in claim 1 wherein the light absorption film comprises a light translucent film.

10. (currently amended): A method of manufacturing a lithography mask blank as claimed in claim 1 wherein the light absorption film comprises MoSiN.

11. (previously presented): A lithography mask as recited in claim 6 wherein mask blank is a phase shift mask blank of a half tone type.